

***IN THE UNITED STATES PATENT AND TRADEMARK OFFICE***

Applicant: Koichi WATANABE et al.

Title: SPUTTERING TARGET AND PROCESS FOR PRODUCING  
Si OXIDE FILM THEREWITH

Appl. No.: 10/573,406

International Filing Date: 09/22/2004

371(c) Date: 03/27/2006

Examiner: Jason Berman

Art Unit: 1795

Confirmation Number: 2973

**RESPONSE TO RESTRICTION REQUIREMENT**

Mail Stop Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

In response to the restriction requirement set forth in the Office Action mailed July 20, 2009, Applicant hereby provisionally elects Group I, Claims 1-3 and 10-11, for examination, without traverse.

Applicants reserve the right to file a divisional application covering the subject matter of the non-elected claims, and/or have additional claims considered in this application as appropriate.

Receipt of the initial Office Action on the merits is awaited.

Respectfully submitted,

Date August 19, 2009

By 

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